

Electronic Supporting Information

**Preparation and application of Cu-doped antimony electrode to
improve the performance of pH measurement in seawater**

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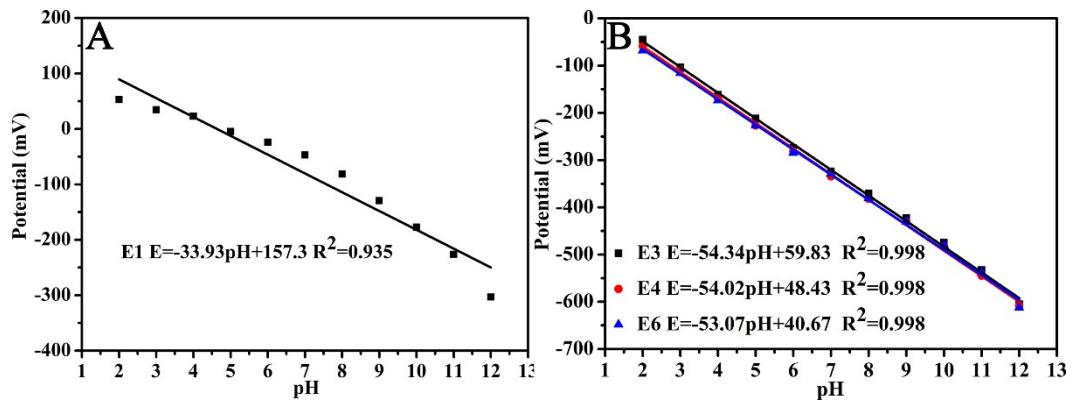


Figure S1 (A) Response curve of E1 electrode in the pH range of 2-12; (B) Response curve of E3,E4 and E6 electrodes in the pH range of 2-12

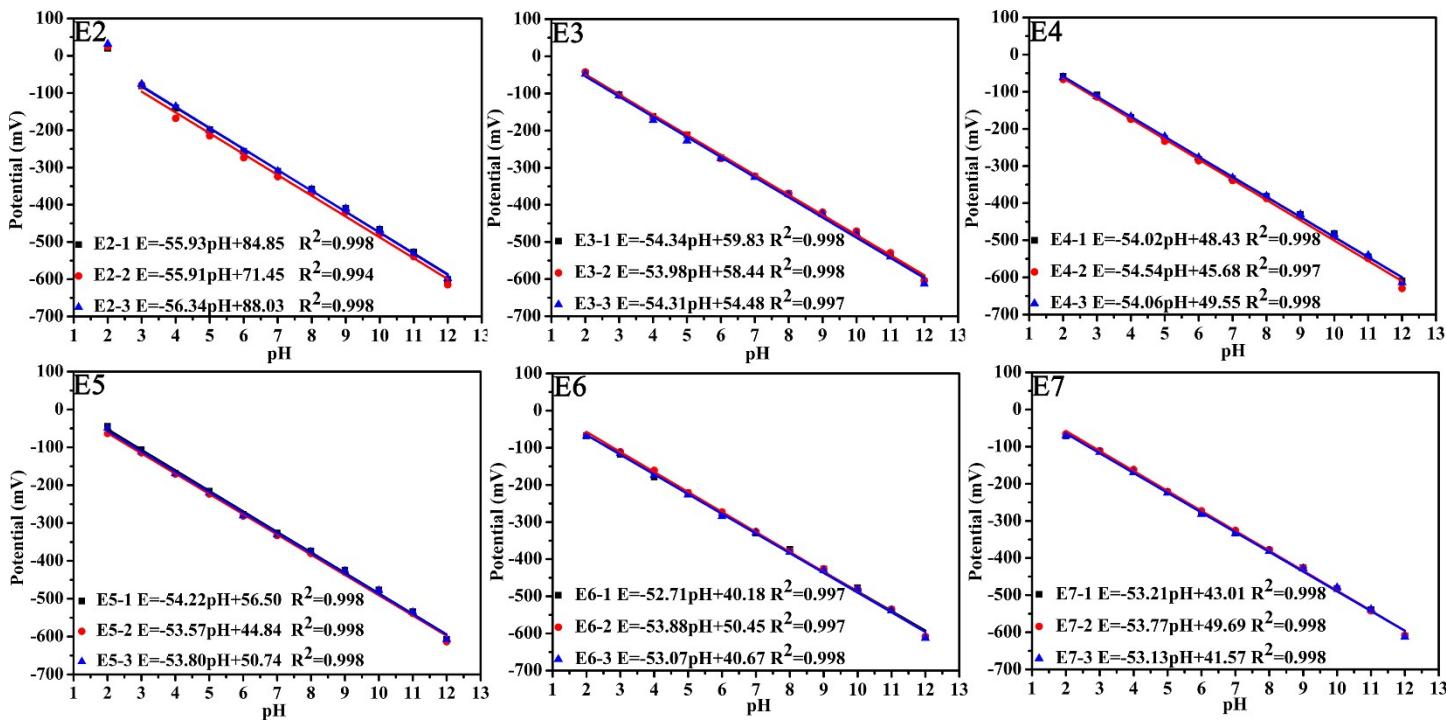


Figure S2 Preparation using the same method, pH response performance of electrodes from different batches

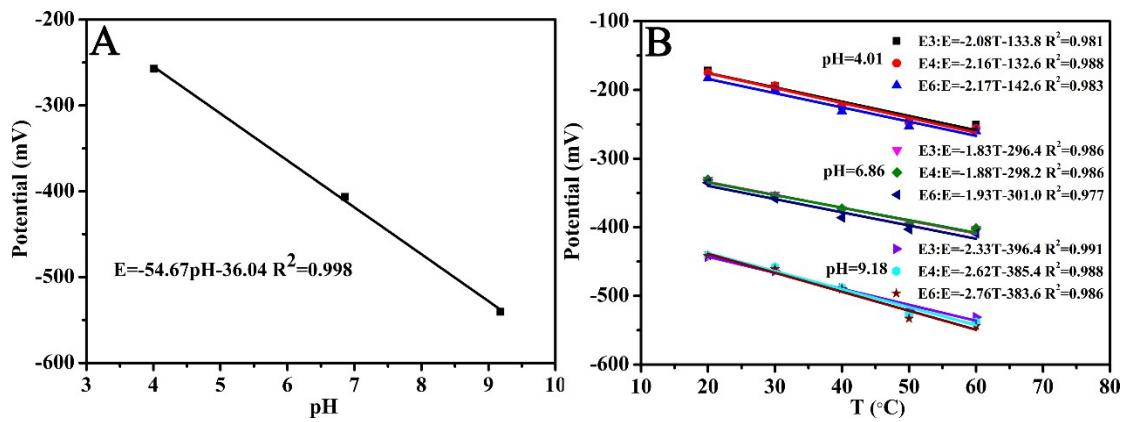


Figure S3 (A) The pH response curve of E5 electrode at 60°C; (B) Temperature coefficients of E3, E4 and E6 electrodes under acidic (pH=4.01), neutral (pH=6.86) and alkaline (pH=9.18) conditions

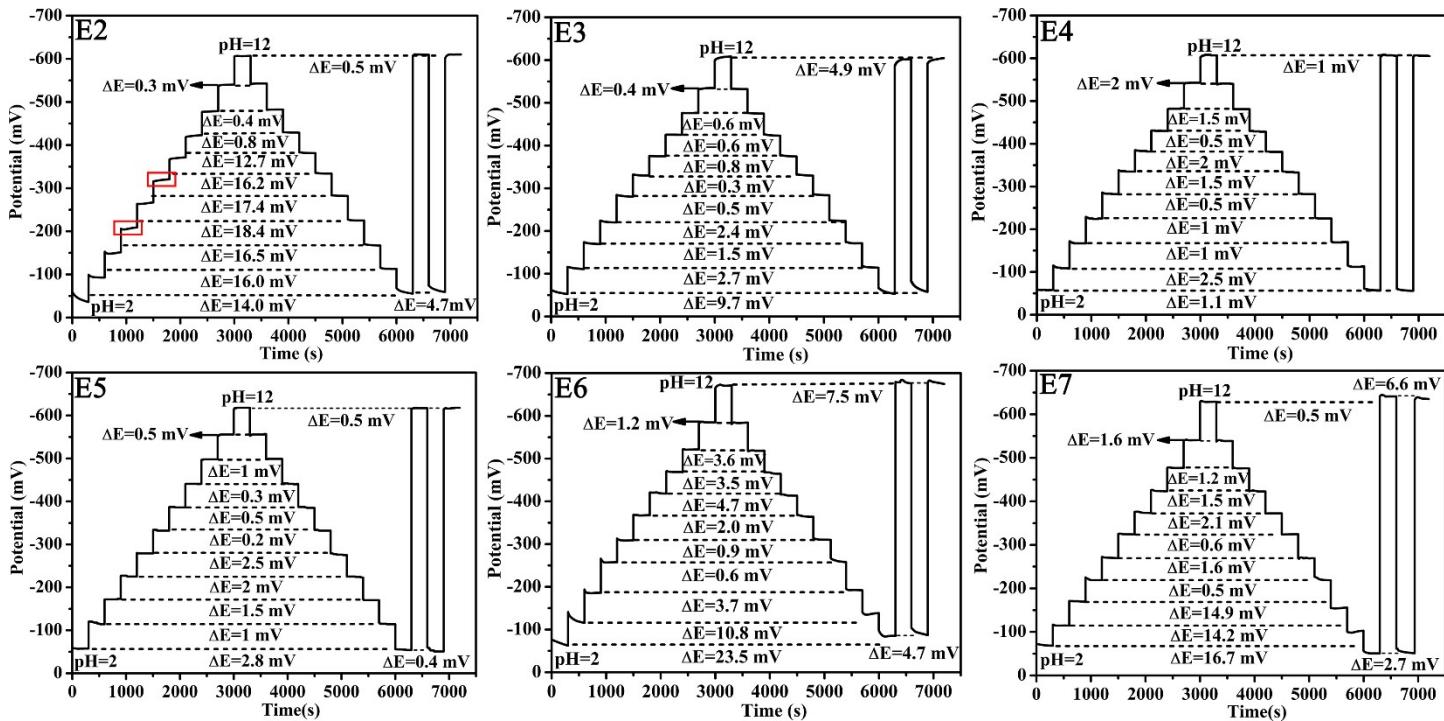


Figure S4 Reversibility and hysteresis of different electrodes in Britton-Robinson buffer solution (pH=2-12-2)

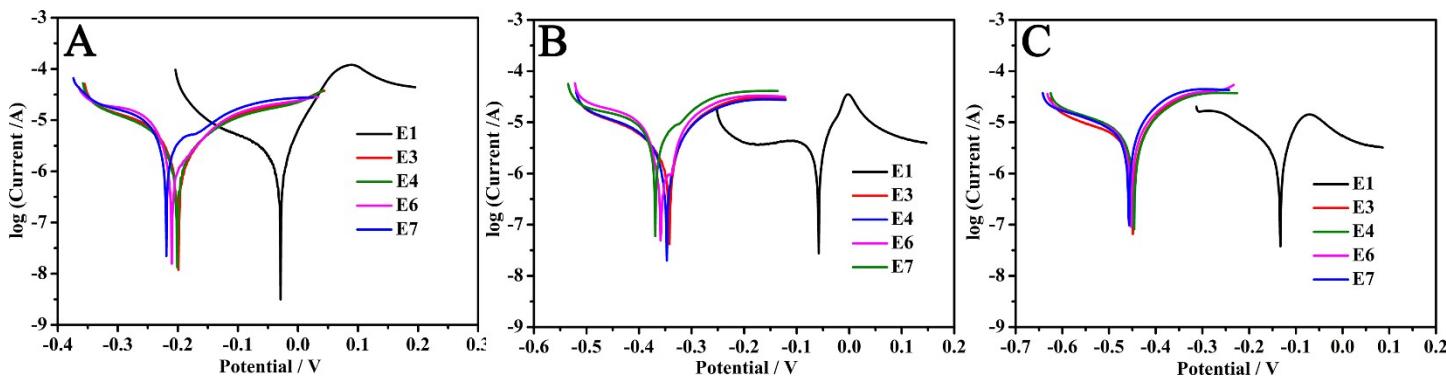


Figure S5 Polarization curves of E1, E3, E4, E6 and E7 electrodes in standard buffer solutions with pH=4.01(A), 6.86(B), and 9.18(C)

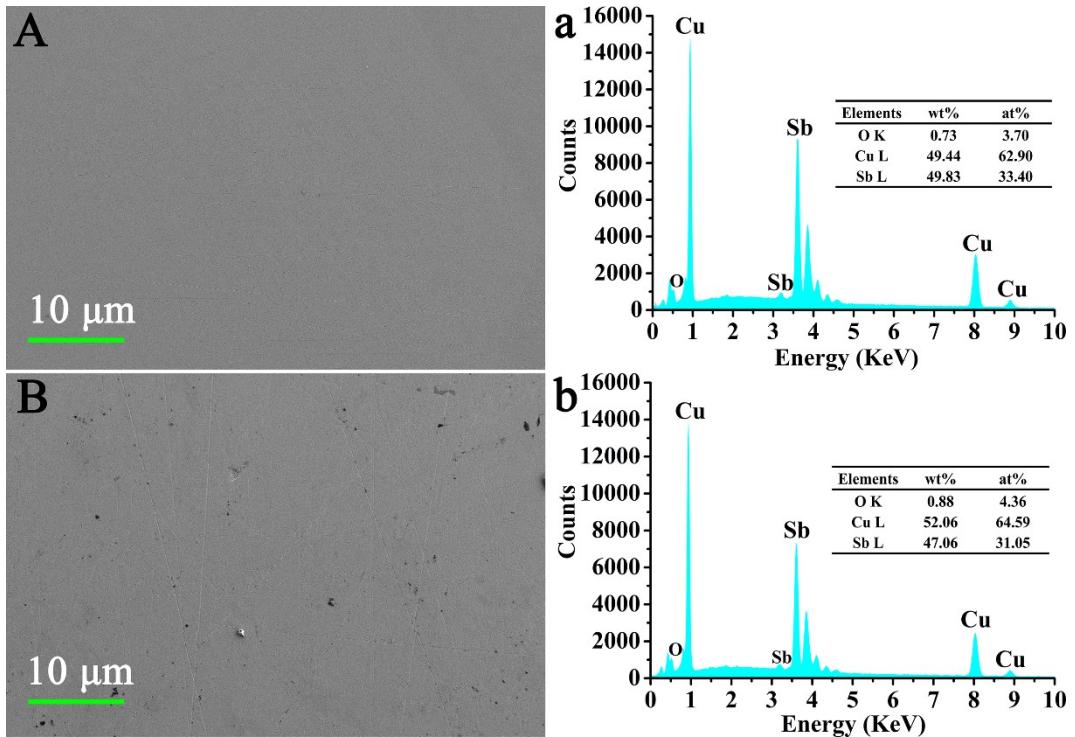


Figure S6 The SEM images and EDS analysis of the E1 electrode surface before and after the electrochemical testing: (A) The SEM images of the E1 electrode surface before the electrochemical testing; (a) The corresponding EDS spectrum and the insert table was the EDS analysis results of the E1 electrode surface before the electrochemical testing; (B) The SEM images of the E1 electrode surface after the electrochemical testing; (b) The corresponding EDS spectrum and the insert table was the EDS analysis results of the E1 electrode surface after the electrochemical testing

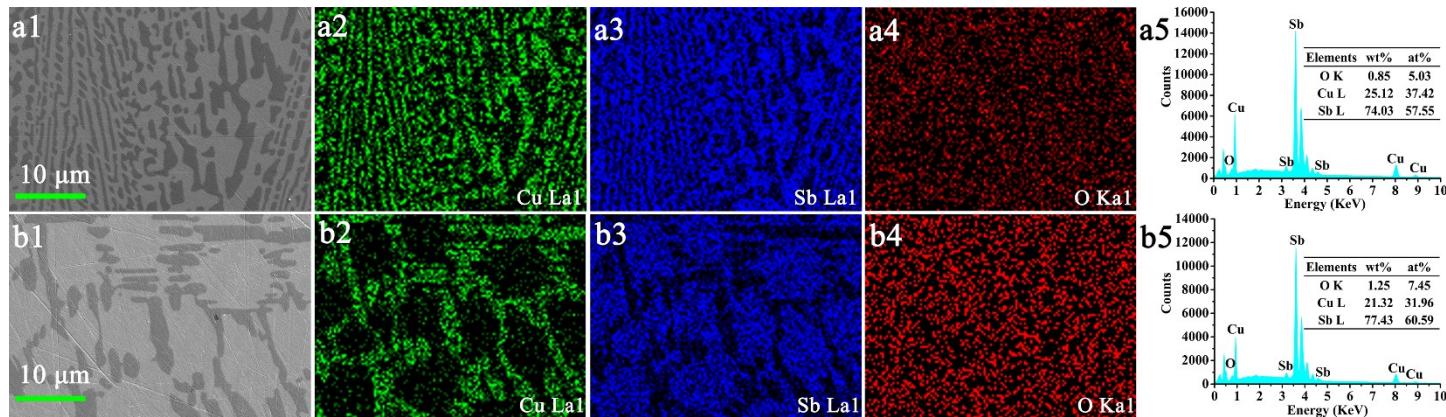


Figure S7 The SEM images and EDS analysis of the E4 and E5 electrodes surface before the electrochemical testing: (a1, b1) The SEM images of the E4 and E5 electrodes surface before the electrochemical testing, respectively; (a2, b2) The copper element distribution map of the E4 and E5 electrodes surface before the electrochemical testing, respectively; (a3, b3) The antimony element distribution map of the E4 and E5 electrodes surface before the electrochemical testing, respectively; (a4, b4) The oxygen element distribution map of the E4 and E5 electrodes surface before the electrochemical testing, respectively; (a5, b5) The corresponding EDS spectrum of the mapping area and the insert table was the EDS analysis results of the E4 and E5 electrodes surface before the electrochemical testing, respectively

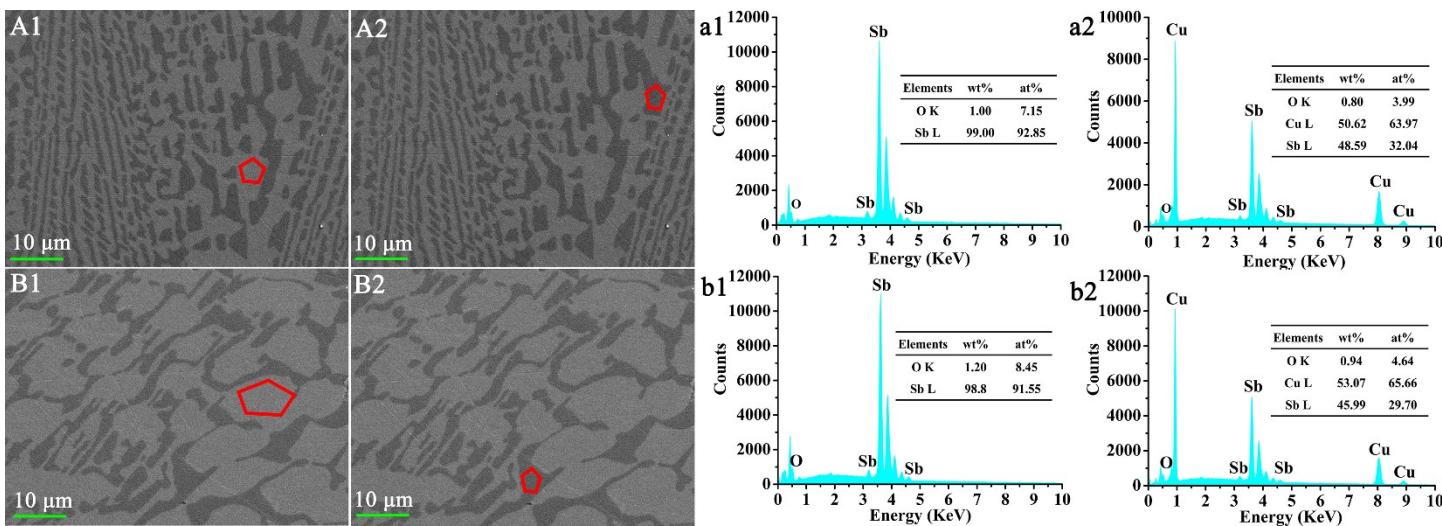


Figure S8 The EDS point analysis of the E3 and E4 electrodes before the electrochemical testing: (A1, A2) the SEM image of the E4 electrode; (a1, a2) The EDS spectra corresponding to the red areas of A1 and A2, respectively and the insert tables were the EDS analysis results; (B1, B2) the SEM image of the E3 electrode; (b1, b2) The EDS spectra corresponding to the red areas of B1 and B2, respectively and the insert tables were the EDS analysis results

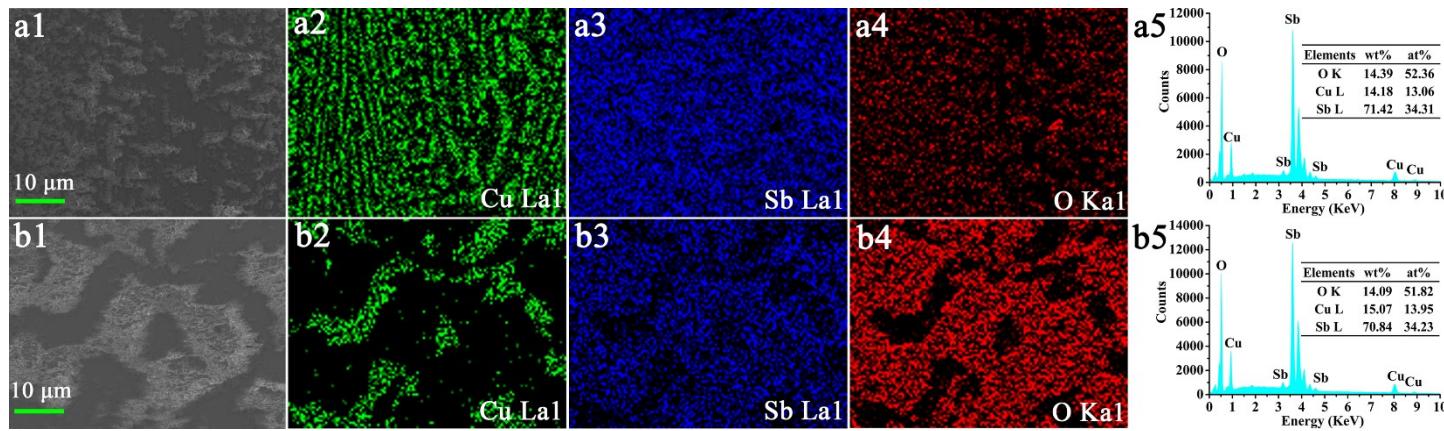


Figure S9 The SEM images and EDS analysis of the E4 and E5 electrodes surface after the electrochemical testing: (a1, b1) The SEM images of the E4 and E5 electrodes surface after the electrochemical testing, respectively; (a2, b2) The copper element distribution map of the E4 and E5 electrodes surface after the electrochemical testing, respectively; (a3, b3) The antimony element distribution map of the E4 and E5 electrodes surface after the electrochemical testing, respectively; (a4, b4) The oxygen element distribution map of the E4 and E5 electrodes surface after the electrochemical testing, respectively; (a5, b5) The corresponding EDS spectrum of the mapping area and the insert table was the EDS analysis results of the E4 and E5 electrodes surface after the electrochemical testing, respectively

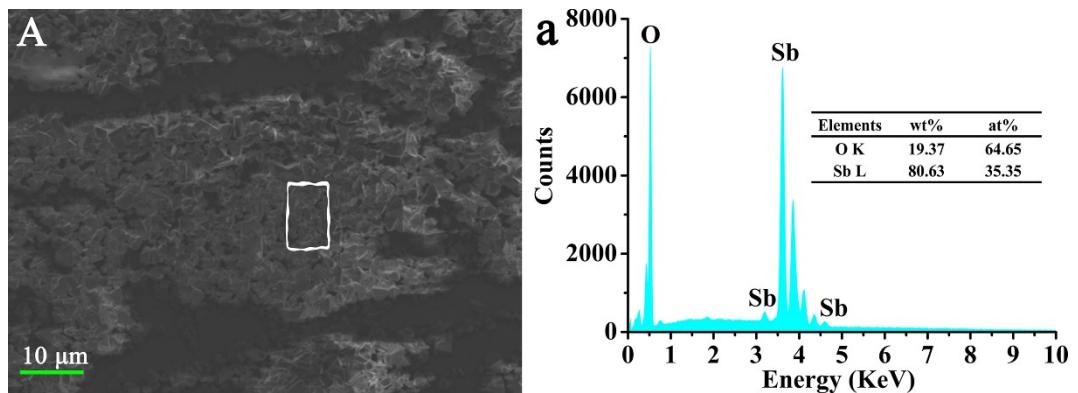


Figure S10 The EDS point analysis of the E5 electrode after the electrochemical testing: (A) The SEM image of the E5 electrode; (a) The EDS spectra corresponding to the White box area of Fig. S5, A, and the insert tables were the EDS analysis results

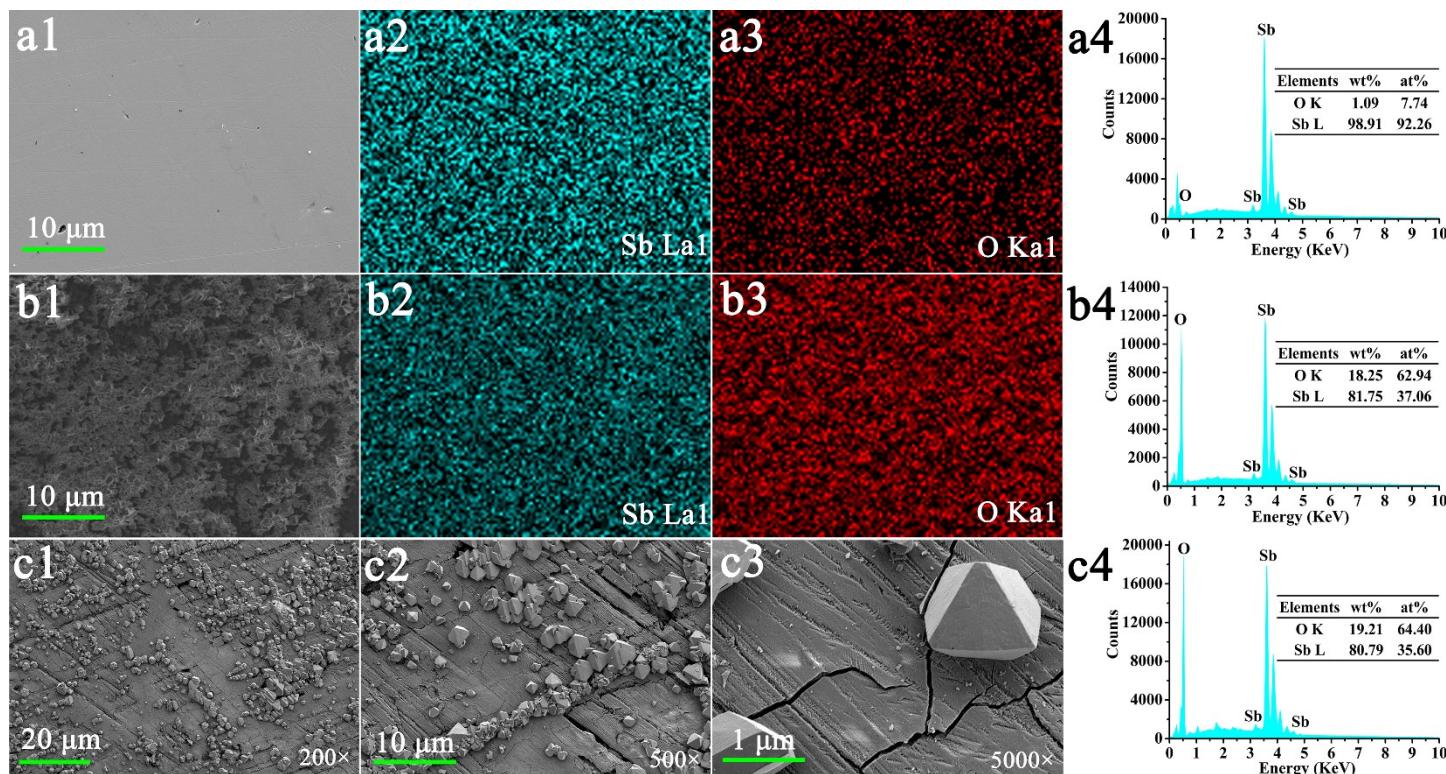


Figure S11 The EDS analysis of the E7 electrode before (a1-a4) and after (b1-b4) the electrochemical testing: (a1 and b1) The SEM images of the E7 electrode before and after the electrochemical testing, respectively; (a2 and b2) The antimony element distribution maps; (a3 and b3) The oxygen element distribution maps; (a4 and b4) The corresponding EDS spectrum of the mapping area and the insert table was the EDS analysis results; (c1 - c3) SEM images at different magnifications after electrochemical testing of pure antimony electrodes; (c4) The corresponding EDS spectrum of the E7 electrode surface and the insert table was the EDS analysis results

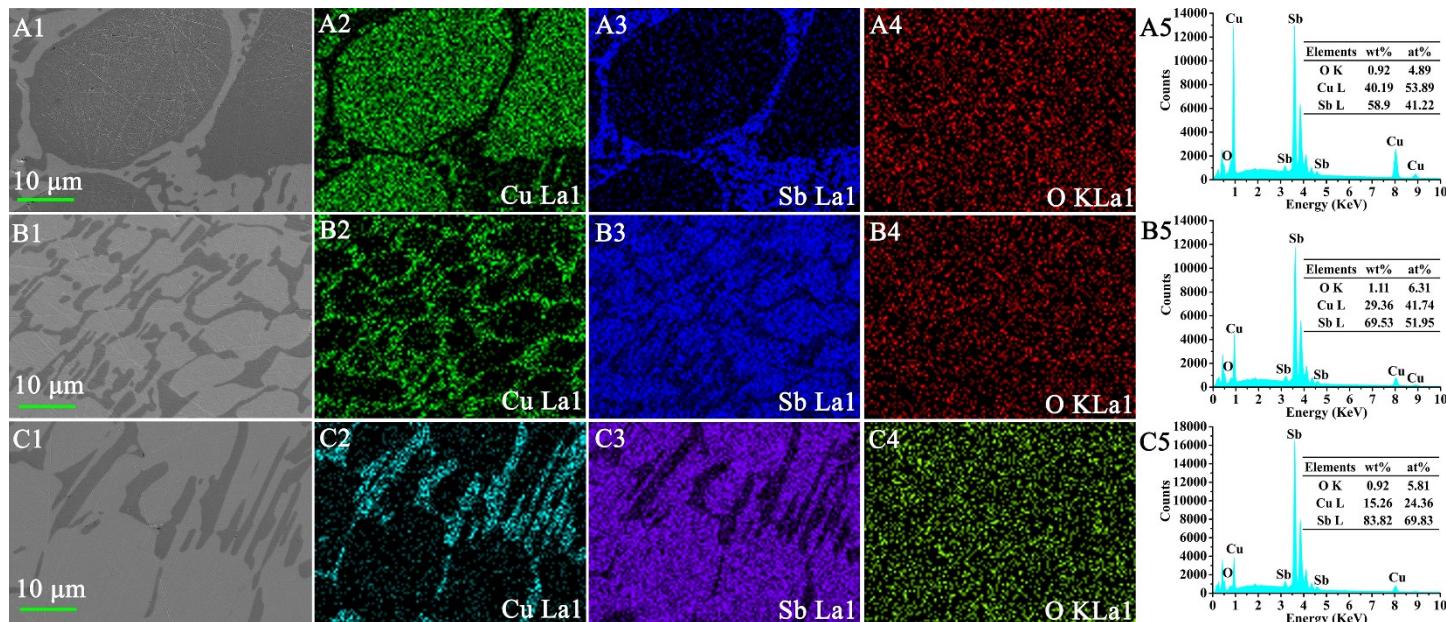


Figure S12 (A) The SEM images and EDS analysis of the E2, E3 and E6 electrodes surface before the electrochemical testing; (A1, B1, and C1) The SEM images of the E2, E3 and E6 electrodes surface before the electrochemical testing; (A2, B2, and C2) The copper element distribution map of the E2, E3 and E6 electrodes; (A3, B3, and C3) The antimony element distribution map of the E2, E3 and E6 electrodes; (A4, B4, and C4) The oxygen element distribution map of the E2, E3 and E6 electrodes; (A5, B5, and C5) The corresponding EDS spectrum of the mapping area and the insert table was the EDS analysis results of the E2, E3 and E6 electrodes

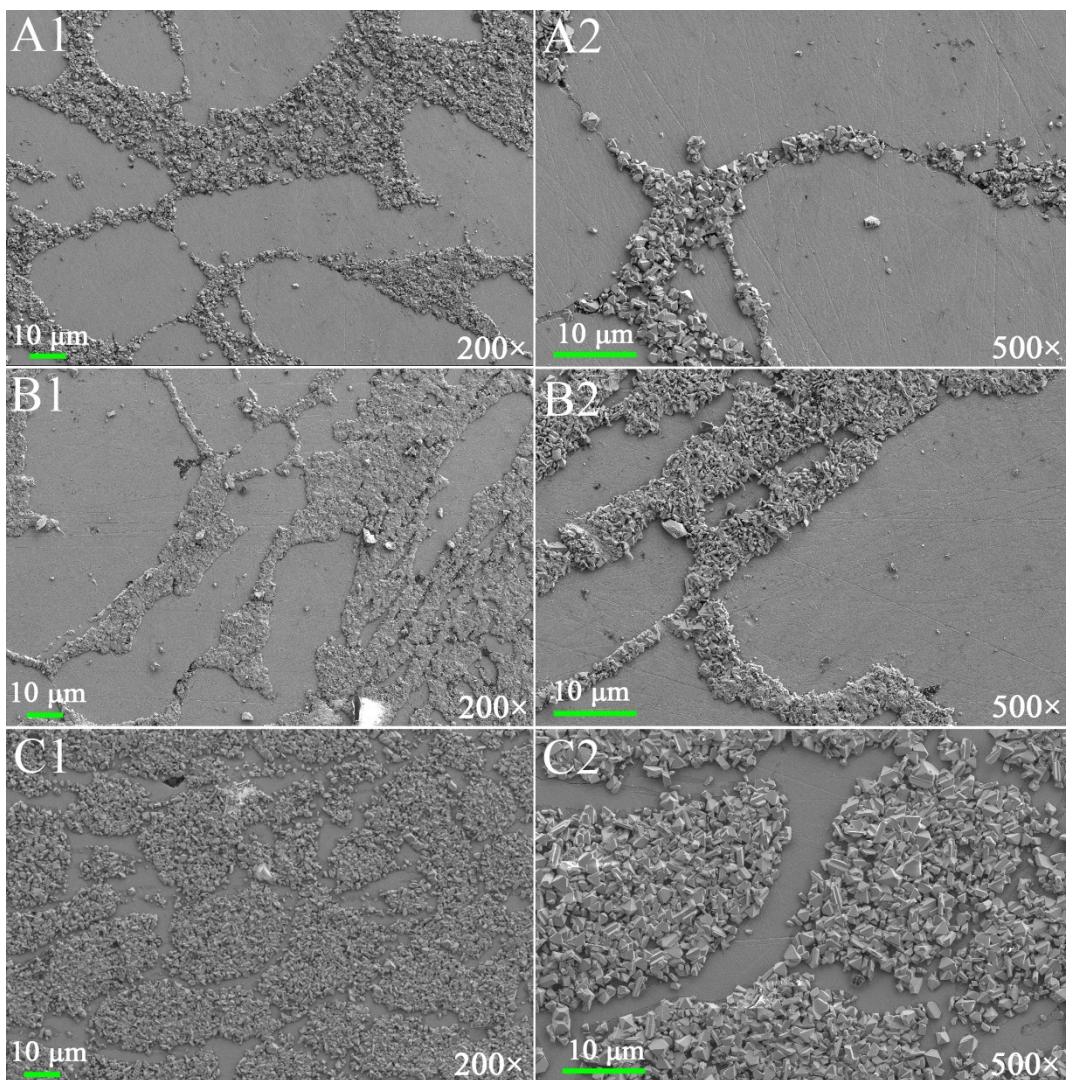


Figure S13 (A1, A2) SEM images at different magnifications after electrochemical testing of E2 electrode; (B1, B2) SEM images at different magnifications after electrochemical testing of E3 electrode; (C1, C2) SEM images at different magnifications after electrochemical testing of E6 electrode

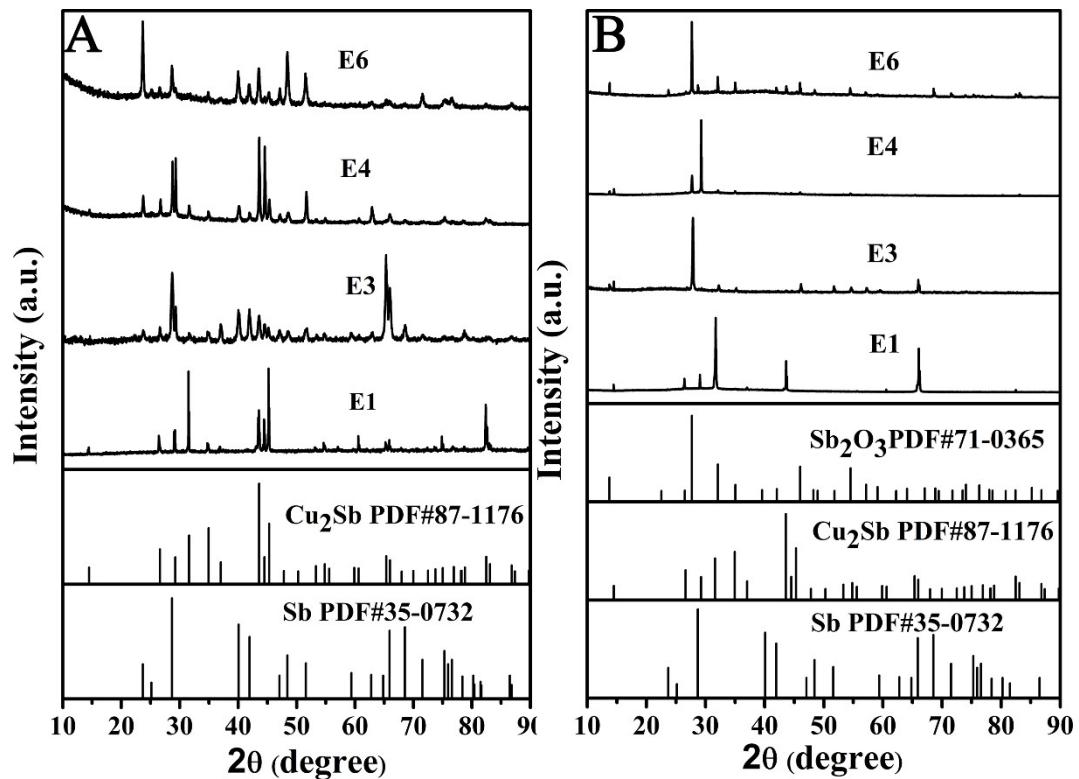


Figure S14 (A) XRD diffraction patterns of E1, E3, E4, and E6 electrodes before electrochemical testing; (B) XRD diffraction patterns of E1, E3, E4, and E6 electrodes after electrochemical testing

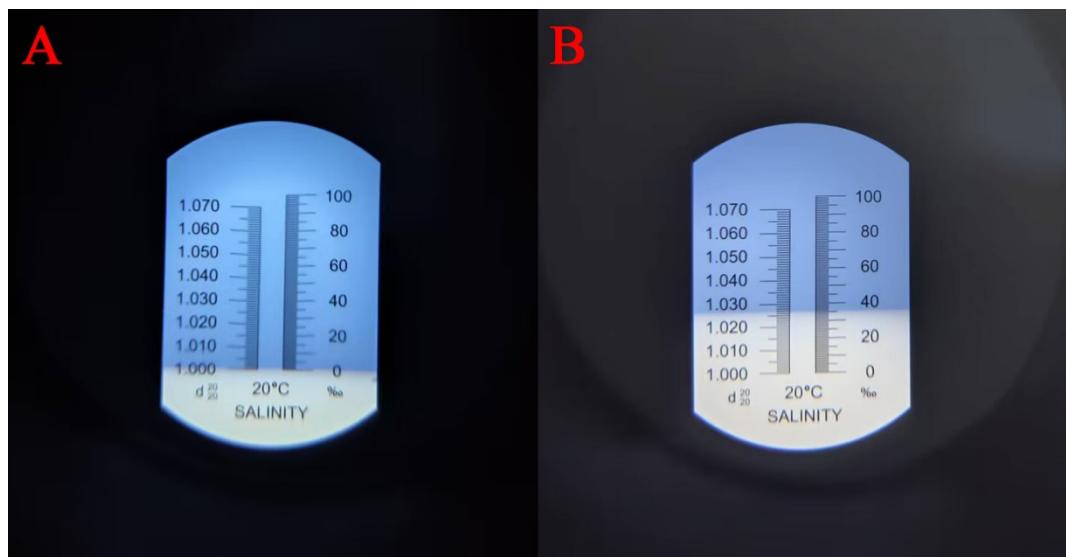


Figure S15 (A) Zero scale line of salinity meter; (B) The reading of salinity meter for testing seawater salinity

Table S1 pH measurement results after adding interfering substances to pH=9.18 standard buffer solution

| Electrode | Solution | | | | | |
|-----------|--|---------------------------|---------------------------|--------------|--------------------------|---|
| | pH 9.18+K ₂ SO ₄ | pH 9.18+MgSO ₄ | pH 9.18+CaCl ₂ | pH 9.18+NaCl | pH 9.18+KNO ₃ | pH 9.18+Na ₂ CO ₃ |
| E2 | 9.16±0.08 | 8.89±0.07 | 8.73±0.07 | 8.95±0.07 | 9.13±0.08 | 10.51±0.06 |
| E3 | 9.13±0.05 | 8.78±0.04 | 8.66±0.06 | 8.91±0.04 | 9.08±0.04 | 10.63±0.03 |
| E4 | 9.15±0.04 | 8.74±0.05 | 8.73±0.04 | 9.01±0.02 | 9.14±0.02 | 10.64±0.05 |
| E5 | 9.21±0.04 | 8.75±0.05 | 8.72±0.04 | 8.95±0.02 | 9.11±0.06 | 10.64±0.06 |
| E6 | 9.19±0.06 | 8.69±0.06 | 8.54±0.04 | 8.96±0.02 | 9.08±0.03 | 10.72±0.06 |
| E7 | 9.16±0.07 | 8.67±0.06 | 8.42±0.05 | 8.91±0.03 | 9.04±0.04 | 10.81±0.07 |
| GE | 9.22±0.03 | 8.81±0.04 | 8.67±0.02 | 9.07±0.02 | 9.18±0.03 | 10.58±0.04 |

Table S2 pH measurement results after adding interfering substances to pH=6.86 standard buffer solution

| Electrode | Solution | | |
|-----------------|--|--------------|--------------------------|
| | pH 6.86+K ₂ SO ₄ | pH 6.86+NaCl | pH 6.86+KNO ₃ |
| E2 | 6.93±0.07 | 6.83±0.06 | 6.91±0.06 |
| E3 | 6.83±0.03 | 6.75±0.05 | 6.85±0.02 |
| E4 | 6.82±0.04 | 6.80±0.03 | 6.85±0.05 |
| E5 | 6.83±0.04 | 6.79±0.04 | 6.81±0.03 |
| E6 | 6.86±0.04 | 6.85±0.06 | 6.87±0.03 |
| E7 | 7.04±0.04 | 6.96±0.05 | 6.97±0.05 |
| Glass Electrode | 6.78±0.03 | 6.68±0.02 | 6.78±0.02 |

Table S3 pH measurement results after adding interfering substances to pH=4.01 standard buffer solution

| Electrode | Solution | | | | |
|-----------------|--|--------------|--------------------------|---------------------------|---------------------------|
| | pH 4.01+K ₂ SO ₄ | pH 4.01+NaCl | pH 4.01+KNO ₃ | pH 4.01+MgSO ₄ | pH 4.01+CaCl ₂ |
| E2 | 4.50±0.07 | 4.21±0.06 | 4.56±0.06 | 4.17±0.05 | 4.19±0.05 |
| E3 | 4.04±0.03 | 3.78±0.05 | 4.08±0.05 | 3.75±0.04 | 3.67±0.04 |
| E4 | 3.90±0.03 | 3.78±0.04 | 4.06±0.05 | 3.68±0.03 | 3.54±0.03 |
| E5 | 3.96±0.03 | 3.79±0.03 | 4.03±0.03 | 3.74±0.03 | 3.51±0.03 |
| E6 | 3.99±0.04 | 3.78±0.03 | 4.05±0.04 | 3.79±0.03 | 3.56±0.03 |
| E7 | 4.1±0.07 | 3.82±0.05 | 4.08±0.06 | 3.8±0.06 | 3.61±0.04 |
| Glass Electrode | 3.91±0.02 | 3.83±0.02 | 3.99±0.03 | 3.71±0.02 | 3.57±0.02 |

Table S4 Polarization parameters of the prepared electrodes immersed in the standard buffer solutions of different pH values

| Electrode | pH 4.01 | | | | | pH 6.86 | | | | | pH 9.18 | | | | |
|-----------|-----------------------------|-----------------------------|--------------------------|---|---------------------------------|-----------------------------|-----------------------------|--------------------------|---|---------------------------------|-----------------------------|-----------------------------|--------------------------|---|---------------------------------|
| | β_{Ano} /mV | β_{Cat} /mV | E_{corr} /mV | I_{corr} /(A·cm ⁻²) | R_p /(Ω·cm ⁻²) | β_{Ano} /mV | β_{Cat} /mV | E_{corr} /mV | I_{corr} /(A·cm ⁻²) | R_p /(Ω·cm ⁻²) | β_{Ano} /mV | β_{Cat} /mV | E_{corr} /mV | I_{corr} /(A·cm ⁻²) | R_p /(Ω·cm ⁻²) |
| E1 | 10.92 | 5.34 | -29 | 3.01E-06 | 7924.3 | 11.17 | 1.36 | -58 | 6.1E-06 | 6225.2 | 6.49 | 5.93 | -133 | 5.99E-06 | 5441.9 |
| E2 | 4.43 | 10.14 | -178 | 3.37E-06 | 9912.7 | 3.38 | 4.80 | -306 | 4.76E-06 | 7468.8 | 5.21 | 3.77 | -445 | 7.16E-06 | 6761.5 |
| E3 | 5.54 | 4.03 | -200 | 4.99E-06 | 9097.4 | 4.89 | 4.54 | -342 | 5.34E-06 | 6515.5 | 4.97 | 3.16 | -449 | 1.06E-05 | 5043.2 |
| E4 | 5.40 | 4.55 | -201 | 5.07E-06 | 8617.6 | 4.95 | 4.08 | -347 | 6.66E-06 | 5901.6 | 4.95 | 3.28 | -446 | 1.18E-05 | 4462.0 |
| E5 | 6.21 | 2.95 | -203 | 6.12E-06 | 7756.5 | 4.77 | 3.79 | -349 | 8.21E-06 | 5758.2 | 5.02 | 2.76 | -446 | 1.19E-05 | 4628.1 |
| E6 | 7.12 | 2.16 | -210 | 6.29E-06 | 7472.5 | 5.78 | 3.03 | -359 | 1.09E-05 | 4623.8 | 4.99 | 3.35 | -453 | 1.23E-05 | 4215.7 |
| E7 | 7.10 | 3.50 | -219 | 9.68E-06 | 4239.1 | 6.24 | 2.44 | -369 | 1.52E-05 | 3284.0 | 4.63 | 3.32 | -457 | 1.53E-05 | 3583.3 |

Table S5 Compositions of the buffer with addition of 0.59 mol·L⁻¹ NaCl

| | Composition (mol L ⁻¹) | | | pH |
|----------|------------------------------------|--------|------|-------|
| | KH ₂ PO ₄ | NaOH | NaCl | |
| Buffer 1 | 0.1000 | | 0.59 | 4.31 |
| Buffer 2 | 0.0900 | 0.0074 | 0.59 | 5.33 |
| Buffer 3 | 0.0630 | 0.0350 | 0.59 | 6.41 |
| Buffer 4 | 0.0519 | 0.0478 | 0.59 | 7.11 |
| | NaHCO ₃ | NaOH | NaCl | |
| Buffer 5 | 0.0455 | 0.0091 | 0.59 | 9.00 |
| Buffer 6 | 0.0363 | 0.0335 | 0.59 | 10.31 |

Table S6 Comparison of the pH electrode in this work with other pH electrodes reported

| Electrode types | Sensitivity (mV/pH) | pH rang e | Response time (s) | Stability | Hysteresis (mV) | Method | References |
|--|------------------------|-----------------|----------------------|---|--------------------|--|------------|
| Sb nanowires | 55.9 | 2-10 | 10 | - | - | focused ion beam based approach | 1 |
| Sb film | 74.0 | 4-9 | < 3 | < 2 mV in 700 s | - | magnetron sputtering and heat treated | 2 |
| Sb film | 67.3 | 4-9 | < 3.5 | < 2 mV in 700 s | <1.3 | magnetron sputtering and thermal annealing | 3 |
| Sb film | 62.57 | 4-9 | 7.1 | 1.60 mV h ⁻¹ | 1.58 | magnetron sputtering | 4 |
| TiO ₂ -Sb-SbO _x films | 68 ± 6 | 2-10 | - | - | - | plasma electrolytic oxidation | 5 |
| Mg-doped Sb ₂ O ₃ membrane | 60.17 | 2-12 | - | 1.99 mV h ⁻¹ | 4.29 | Sputtering and rapid thermal annealing | 6 |
| Ir-IrO _X | -56± 1 | 2-10 | 1 | < 0.65 mV in 48 h Acidity 0.14 mV h ⁻¹ Neutral -0.76 mV h ⁻¹ Alkalinity 57.75 mV h ⁻¹ | - | Carbonate-melt oxidation | 7 |
| IrO ₂ membrane | -74.45 | 2-12 | | | 4.21-16.97 | Electrodeposition | 8 |
| RuO ₂ | -55.3 | 2-6 | 55 ± 23 | 7.2 mV h ⁻¹ | <1 | Laser-etched sputter deposited | 9 |
| RuO ₂ -CuO | 54.3 ± 6.4 | 3-11 | - | 5 mV h ⁻¹ | 5 ± 2 | Screen printing | 10 |
| PdO thin film | -62.87 | 2-12 | | 2.32 mV h ⁻¹ | 7.9 | Reactive electron beam evaporation | 11 |
| Pd/ PdO films | 64.71± 0.56 | 2-12 | < 18 | 3.25 mV h ⁻¹ | < 8 | Solution processing | 12 |
| Cu-Sb alloy rod | -54.38 | 2-12 | 1 | 0.07-0.12 mV h ⁻¹ | <3 | Melt casting method | This work |

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